

09960441

1911 (measur\$4 near3 pressure) same (wafer substrate)
212 (measur\$4 near3 pressure) same (wafer substrate) same (capacit\$4)
29 ((measur\$4 near3 pressure) same (wafer substrate) same (capacit\$4)) and 438/\$.ccls.
51 (appl\$4 near2 pressure near3 (wafer substrate)) same (measur\$4 near3 pressure)
22 (wafer substrate) same (measur\$4 near3 pressure near3 processing)
23 (438/14.ccls. 438/15.ccls. 438/16.ccls. 438/17.ccls. 438/18.ccls.) and ((measur\$4 near3 pressure) same (wafer substrate))
10 (438/4.ccls. 438/5.ccls. 438/6.ccls. 438/7.ccls. 438/8.ccls. 438/10.ccls. 438/11.ccls. 438/12.ccls. 438/13.ccls.) and ((measur\$4 near3 pressure) same (wafer substrate))
23 (capacit\$4 near3 sens\$4 near4 pressure near5 measur\$4) same (wafer substrate)
13 (capacit\$4 near3 pressure near2 sensor) and (pressure near3 data near3 stor\$3)
0 (438/14.ccls. 438/15.ccls. 438/16.ccls. 438/17.ccls. 438/18.ccls.) and (pressure near2 sensor) and (pressure near3 data near3 stor\$3)
1 (438/14.ccls. 438/15.ccls. 438/16.ccls. 438/17.ccls. 438/18.ccls.) and (pressure near3 data near3 stor\$3)
0 (438/14.ccls. 438/15.ccls. 438/16.ccls. 438/17.ccls. 438/18.ccls.) and ((measur\$4 near3 pressure) same (stor\$3 near3 data))
4 (measur\$4 near3 pressure) adj2 (on applied) adj2 (wafer substrate)
89 ((measur\$4 near3 pressure) same (wafer substrate)) and (sensor near3 ((wafer substrate) near3 surface))
190 430/50.ccls.
61 430/51.ccls.
149 430/52.ccls.
165 430/53.ccls.